

*JPW*

In re the Application of: **Miwa KOZAWA et al.**

Group Art Unit: **1756**

Application Number: **10/720,097**

Examiner: **Daborah Chacko Davis**

Filed: **November 25, 2003**

Confirmation Number: **4454**

For: **PROCESS FOR FORMING RESIST PATTERN, SEMICONDUCTOR  
DEVICE AND FABRICATION THEREOF**

Attorney Docket Number: **032132**

Customer Number: **38834**

**RESPONSE TO RESTRICTION REQUIREMENT**

Commissioner for Patents  
P. O. Box 1450  
Alexandria, VA 22313-1450

October 5, 2006

Sir:

This paper is submitted in response to the Official Action dated September 7, 2006.

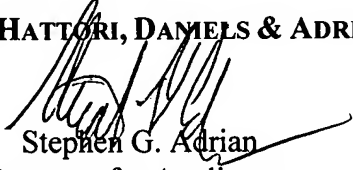
In the Action, restriction is required between Groups I - II.

Applicants hereby elect the subject matter of Group I (Claims 1-20) for prosecution in this application. This election is made without traverse, and it is understood that Applicants' rights to the filing of a divisional application directed to the non-elected subject matter under 35 U.S.C. §120 and 35 U.S.C. §121 are retained.

Response to Restriction Requirement  
Application No. 10/720,097  
Attorney Docket No. 032132

If this paper is not timely filed, Applicants respectfully petition for an appropriate extension of time. The fees for such an extension or any other fees that may be due with respect to this paper may be charged to Deposit Account No. 50-2866.

Respectfully submitted,  
**WESTERMAN, HATTORI, DANIELS & ADRIAN, LLP**



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